Docket Number (Optional) Application Number **SETI-0006** INFORMATION DISCLOSURE CITATION Applicant(s) (Use several sheets if necessary) Fareed et al. Filing Date Group Art Unit U.S. PATENT DOCUMENTS EXAMINER REF DOCUMENT NUMBER DATE FILING DATE NAME CLASS SUBCLASS INITIAL IF APPROPRIATE US006359292B1 03-2002 Sugawara et al. US006316793B1 11-2001 Sheppard et al. US005981977A 11-1999 Furukawa et al. US005851905A 12-1998 McIntosh et al. FOREIGN PATENT DOCUMENTS REF DOCUMENT NUMBER DATE COUNTRY Translation CLASS SUBCLASS YES NO OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.) "High-Power Microwave GaN/AlGaN HEMT's on Semi-Insulating Silicon Carbide Substrates," S. T. Sheppard et al., IEEE Electron Device Letters, Vol. 20, No. 4, April 1999, pp. 161-163.

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